





## RF Surface Resistance Measurements on Planar Samples at STFC

9<sup>th</sup> IFAST WP9 Meeting 18<sup>th</sup> April 2023

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# **Facility Reminder**







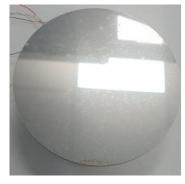


# The Choke Cavity Facility

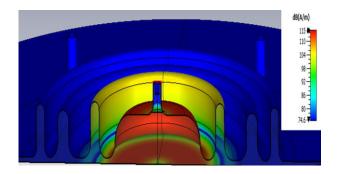
- Two part test cavity in LHe-free cryostat:
  - Bulk Nb choke cavity
  - Planar disk **90 130 mm** diameter, 1 – 10 mm thickness
- **RF-DC** compensation  $\rightarrow R_s(T, B)$
- VNA measurements  $\rightarrow \Delta f \rightarrow \Delta \lambda$
- **Parameters:** 
  - $f_0 = 7.8 \text{ GHz}$
  - $T_{\text{Sample}} \ge 4 \text{ K}$
  - RF Power up to 1 W (for now!)
  - $B_{\text{sample, pk}} \leq 1 \text{ mT}$



**Choke cavity** 



Planar disk



**B**-fields

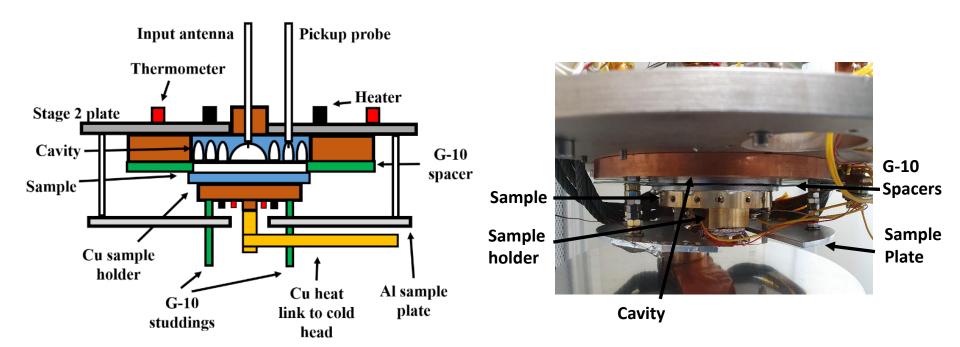








## The Choke Cavity Facility



1 sample test  $(R_s(T))/2$  days









# Cu Samples





**Diamond Turned (DT) from RAL**  $(S_a \sim 2-3 \text{ nm}, S_q \sim 5-6 \text{ nm})$ 





Metallographic Polishing (MP) from IJCLab courtesy of D. Longuevergne & O. Hryhorenko  $(S_a \sim 20 \text{ nm, Ave } S_7 \sim 2.5 \text{ } \mu\text{m})$ 



**EP, SUBU, EP + SUBU from INFN** courtesy of E. Chyhyrynets and C. Pira



Samples are indium brazed to sample holder under vacuum at ~ 160 °C









# RF Measurements of a Bulk Nb Sample

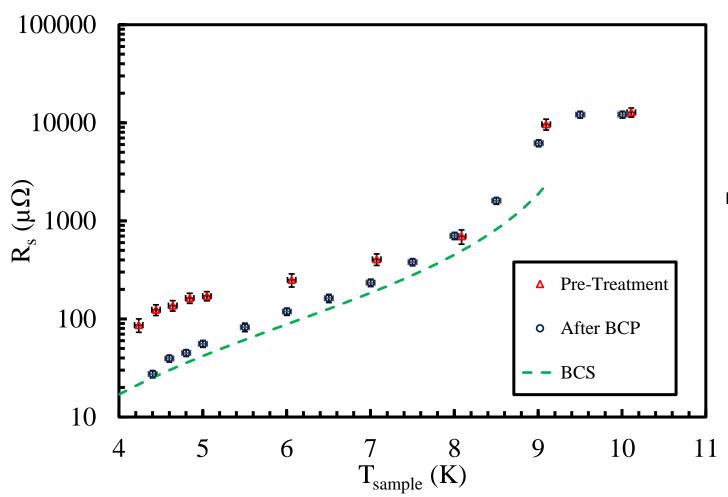








### **Bulk Nb**





Bulk Nb: RRR = 300, BCP with 60-100 μm removed courtesy of E. Chyhyrynets

\* 4 more bulk Nb (RRR = 300) available for treatment









# RF Measurements of Nb on Cu Samples









### Nb on Cu Samples Tested

Sample	Substrate Preparation	Deposition Temperature (°C)	~ Thickness (μm)	
Effect of film thickness with DC magnetron				
1	DT	300 - 350	0.6	
2	DT	300 - 350	1.2	
Effect of deposition temperature with HiPIMS				
3	DT	400 - 450	3	
4	DT	RT	3	
5	DT	300 - 350	3	

<sup>\*</sup> Surface analysis to be shown at 10th meeting

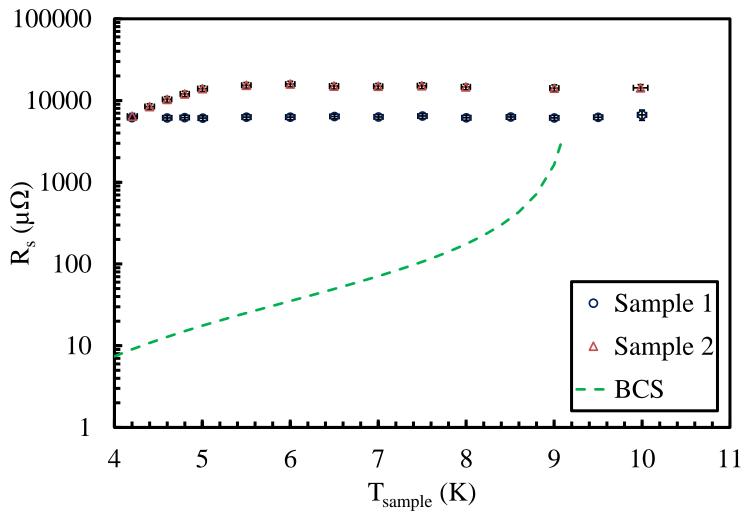


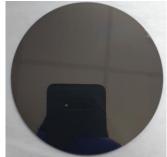




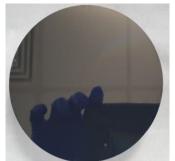


# Samples 1 & 2





Sample 1: DC magnetron, 300 -350 °C, ~ 0.6 μm



Sample 2: DC magnetron, 300 -350 °C, ~ 1.2 μm

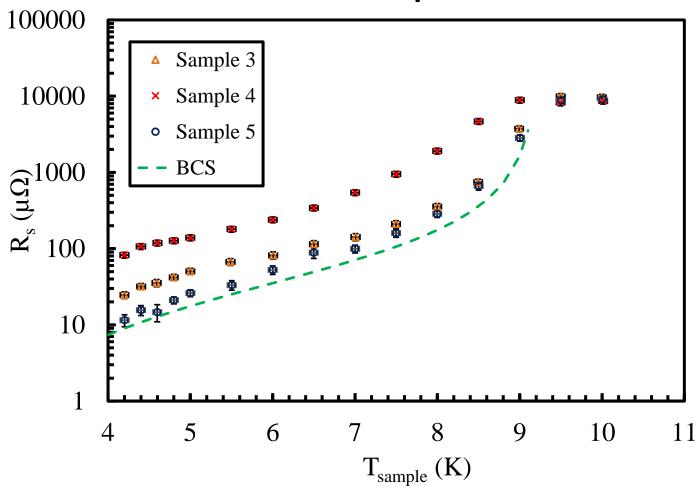


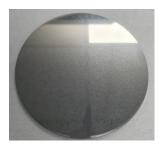






# Samples 3 - 5

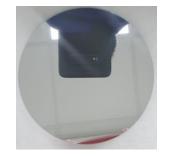




**Sample 3:**  $400 - 450 \,^{\circ}\text{C}$ , ~  $3 \, \mu m$ 



**Sample 4:** RT, ~ 3 μm



**Sample 5:** 300 – 350 °C, ~ 3 μm

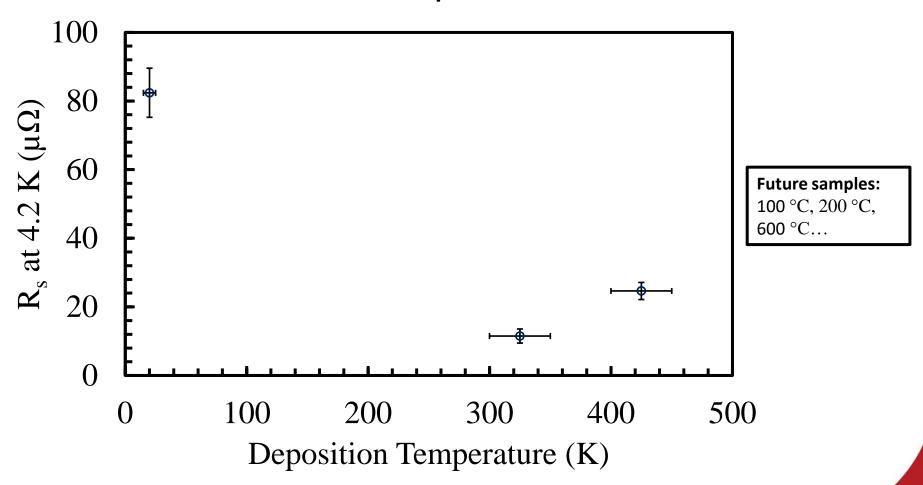








# Samples 3 – 5: towards optimising deposition temperature











# **Future Nb Samples**

Sample	Substrate Preparation	Deposition Temperature (°C)	Thickness (μm)	
Effect of deposition temperature with HiPIMS				
3	DT	400 - 450	~ 3	
4	DT	RT	~ 3	
5	DT	300 - 350	~ 3	
6	DT	600-650	~ 3	
7	DT	100	~ 3	
8	DT	200	~ 3	
Effect of HiPIMS + positive kick				
	DT	?	~ 3	
Effect of substrate preparation				
	MP, EP, SUBU, EP + SUBU	?	~ 3	









# RF Measurements of a Nb<sub>3</sub>Sn Sample

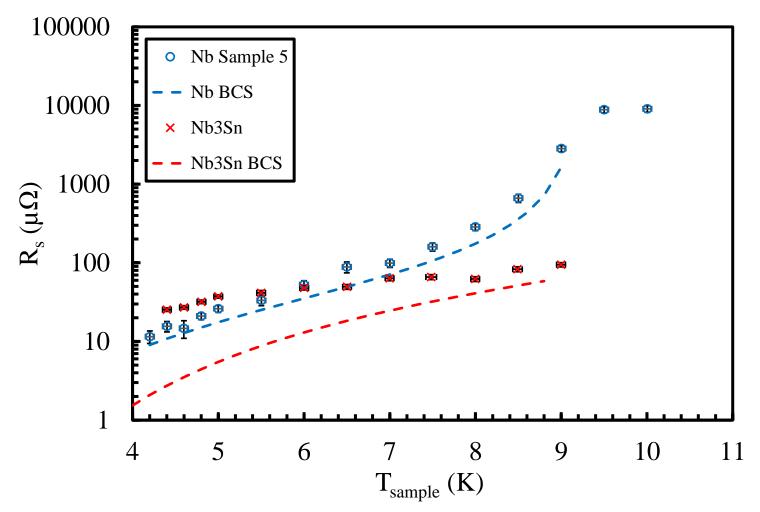


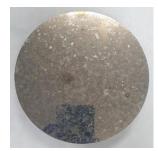






# Nb<sub>3</sub>Sn Sample





Nb<sub>3</sub>Sn Sample: DC magnetron, ~ 600°C, ~ 600 nm









## **Next Steps**



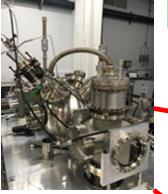






# From planar samples to real cavities





#### 3 sets of samples:













RF test

















### **Current Status & Future Plans**

- 1. Optimise parameters of Nb thin films → Baseline for multilayers
- 2. Continue Nb<sub>3</sub>Sn, NbTiN, (& V<sub>3</sub>Si) single layer studies
- 3. Multilayers (on TF Nb and/or bulk Nb)
- Cut samples → MFP (Liam) & surface analysis (Reza/Chris) etc
- Test IJCLab treated bulk Nb 2 choke cavity
- Move to an RF bunker → higher peak fields (overlapping with QPR)
- Happy to accept samples on disks 90-130 mm diameter (up to 10 mm thickness)
  - Can provide unpolished or polished (mainly DT) Cu
  - Contact: <u>daniel.seal@cockcroft.ac.uk</u>
- Potential for laser treatment at RTU and/or flash at HZDR?









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CEA: C. Antoine







# Thank you for listening

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